

APPENDIX I:

THE SUBSTITUTE SECTION(S) OF THE SPECIFICATION (clean version):

On page 3:

- Delete the paragraph beginning in indicated line 6 and ending in indicated line 8 and insert in its stead:

The rectification column is operated under atmospheric pressure to a reduced pressure of 0.1 atmosphere, preferably at from 0.8 to 1.0 atmosphere. It has also proven suitable to operate the rectification column at from 0.2 to 0.7.

A P P E N D I X II:

THE CHANGE(S) IN THE SPECIFICATION (version with markings):

On page 3:

- The paragraph beginning in indicated line 6 and ending in indicated line 8 has been amended as indicated in the following:

The rectification column is operated under atmospheric pressure to a reduced pressure of 0.1 atmosphere, preferably at from 0.8 to 1.0 atmosphere. It has also proven suitable to operate the rectification column at from 0.2 to 0.7.

APPENDIX III:

THE LISTING OF CLAIMS (version with markings):

1. (currently amended) A process for working up [solutions] a solution of hydroxylamine and amines, [wherein] which comprises passing the solution into a rectification column, and stripping the hydroxylamine [is stripped] from the [hydroxylamine-containing] solution by the countercurrent method with steam to obtain a top product comprising aqueous hydroxylamine and a bottom product comprising amines.
2. (canceled)
3. (canceled)
4. (currently amended) A process as claimed in claim [2] 1, wherein the rectification column is operated at from 0.1 to 1.0 atmosphere.
5. (currently amended) A process as claimed in claim [2] 1, wherein [some] a fraction of the bottom product is vaporized [again] by means of an evaporator and the [vaporous fractions are] vaporized fraction is recycled to the rectification column.
6. (currently amended) A process as claimed in claim [2] 1, wherein water is added to [the liquid phase of] the rectification column.
7. (previously submitted) A process as claimed in claim 4, wherein the rectification column is operated at from 0.8 to 1.0 atmosphere.
8. (previously submitted) A process as claimed in claim 6, wherein the water is passed into the bottom of the rectification column.
9. (currently amended) A process as claimed in claim 1, wherein the solution is [from the electronics industry] a solution used for cleaning electronic components.
10. (currently amended) A process for working up a solution of hydroxylamine and amines,
wherein the hydroxylamine is stripped from the [hydroxylamine-containing] solution with steam,
wherein the solution is passed into a rectification column and steam is passed counter-currently through the column, whereby a top product comprising aqueous hydroxylamine and a bottom product comprising amines are obtained, and

wherein the top product is condensed and is partly recycled to the rectification column with a reflux ratio of less than 0.5.

11. (previously submitted) A process as claimed in claim 10, wherein the rectification column is operated at from 0.1 to 1.0 atmosphere.
12. (previously submitted) A process as claimed in claim 11, wherein the rectification column is operated at from 0.8 to 1.0 atmosphere.
13. (currently amended) A process as claimed in claim 10, wherein [some] a fraction of the bottom product is vaporized [again] by means of an evaporator and the [vaporous fractions are] vaporized fraction is recycled to the rectification column.
14. (currently amended) A process as claimed in claim 10, wherein water is added to [the liquid phase of] the rectification column.
15. (previously submitted) A process as claimed in claim 14, wherein the water is passed into the bottom of the rectification column.
16. (currently amended) A process as claimed in claim 10, wherein the solution is [from the electronics industry] a solution used for cleaning electronic components.

APPENDIX IV:

THE AMENDED CLAIMS (clean version):

1. (currently amended) A process for working up a solution of hydroxylamine and amines, which comprises passing the solution into a rectification column, and stripping the hydroxylamine from the solution by the countercurrent method with steam to obtain a top product comprising aqueous hydroxylamine and a bottom product comprising amines.
2. (canceled)
3. (canceled)
4. (currently amended) A process as claimed in claim 1, wherein the rectification column is operated at from 0.1 to 1.0 atmosphere.
5. (currently amended) A process as claimed in claim 1, wherein a fraction of the bottom product is vaporized by means of an evaporator and the vaporized fraction is recycled to the rectification column.
6. (currently amended) A process as claimed in claim 1, wherein water is added to the rectification column.
7. (previously submitted) A process as claimed in claim 4, wherein the rectification column is operated at from 0.8 to 1.0 atmosphere.
8. (previously submitted) A process as claimed in claim 6, wherein the water is passed into the bottom of the rectification column.
9. (currently amended) A process as claimed in claim 1, wherein the solution is a solution used for cleaning electronic components.
10. (currently amended) A process for working up a solution of hydroxylamine and amines,
wherein the hydroxylamine is stripped from the solution with steam,
wherein the solution is passed into a rectification column and steam is passed counter-currently through the column, whereby a top product comprising aqueous hydroxylamine and a bottom product comprising amines are obtained, and
wherein the top product is condensed and is partly recycled to the rectification column with a reflux ratio of less than 0.5.

11. (previously submitted) A process as claimed in claim 10, wherein the rectification column is operated at from 0.1 to 1.0 atmosphere.
12. (previously submitted) A process as claimed in claim 11, wherein the rectification column is operated at from 0.8 to 1.0 atmosphere.
13. (currently amended) A process as claimed in claim 10, wherein a fraction of the bottom product is vaporized by means of an evaporator and the vaporized fraction is recycled to the rectification column.
14. (currently amended) A process as claimed in claim 10, wherein water is added to the rectification column.
15. (previously submitted) A process as claimed in claim 14, wherein the water is passed into the bottom of the rectification column.
16. (currently amended) A process as claimed in claim 10, wherein the solution is a solution used for cleaning electronic components.